



Ultra-low work function of caesiated surfaces and impact of specific hydrogen plasma species

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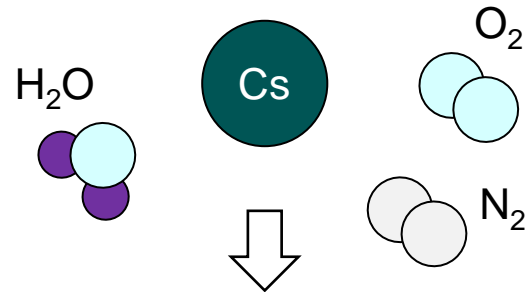


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Surface caesiation for the enhancement of H^- production

Increase of negative ionization yield of H and H_x^+ on surfaces by decreasing the work function
→ Work function decrease of extraction electrode surface at ion sources via Cs adsorption

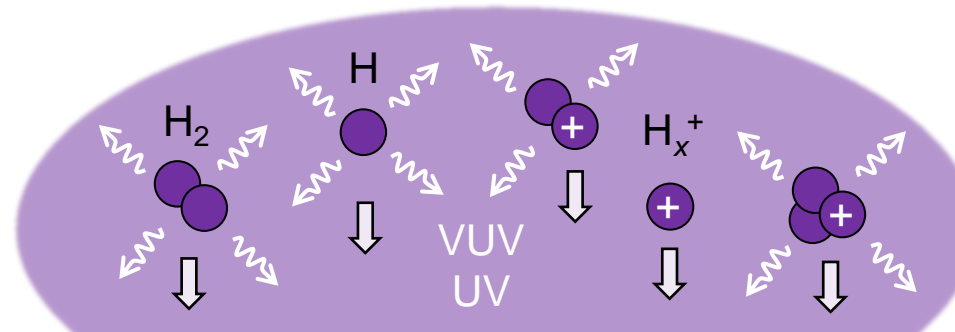
Caesiation in non-UHV:
Co-deposition of Cs and residual gases



Non-pure Cs layer

Refractory metal (Mo)

Plasma interaction with caesiated surfaces:
Cs redistribution, change of chemical composition



Non-pure Cs layer

Refractory metal (Mo)

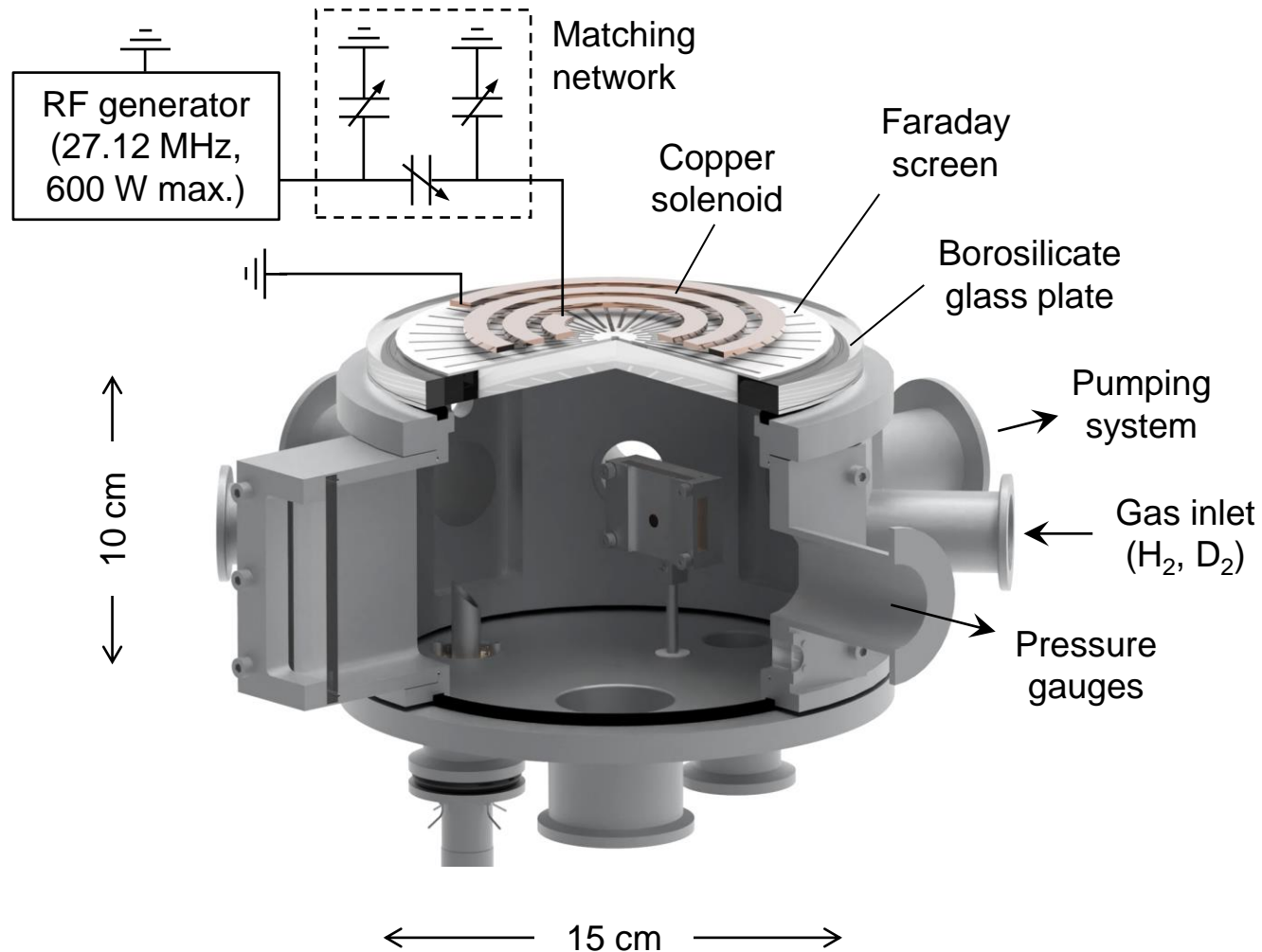


Pronounced temporal work function dynamics

S. Cristofaro *et al.*, *Plasma Res. Express* 2, 035009 (2020)

Experimental setup ACCesS

ICP experiment equipped with in situ work function diagnostic



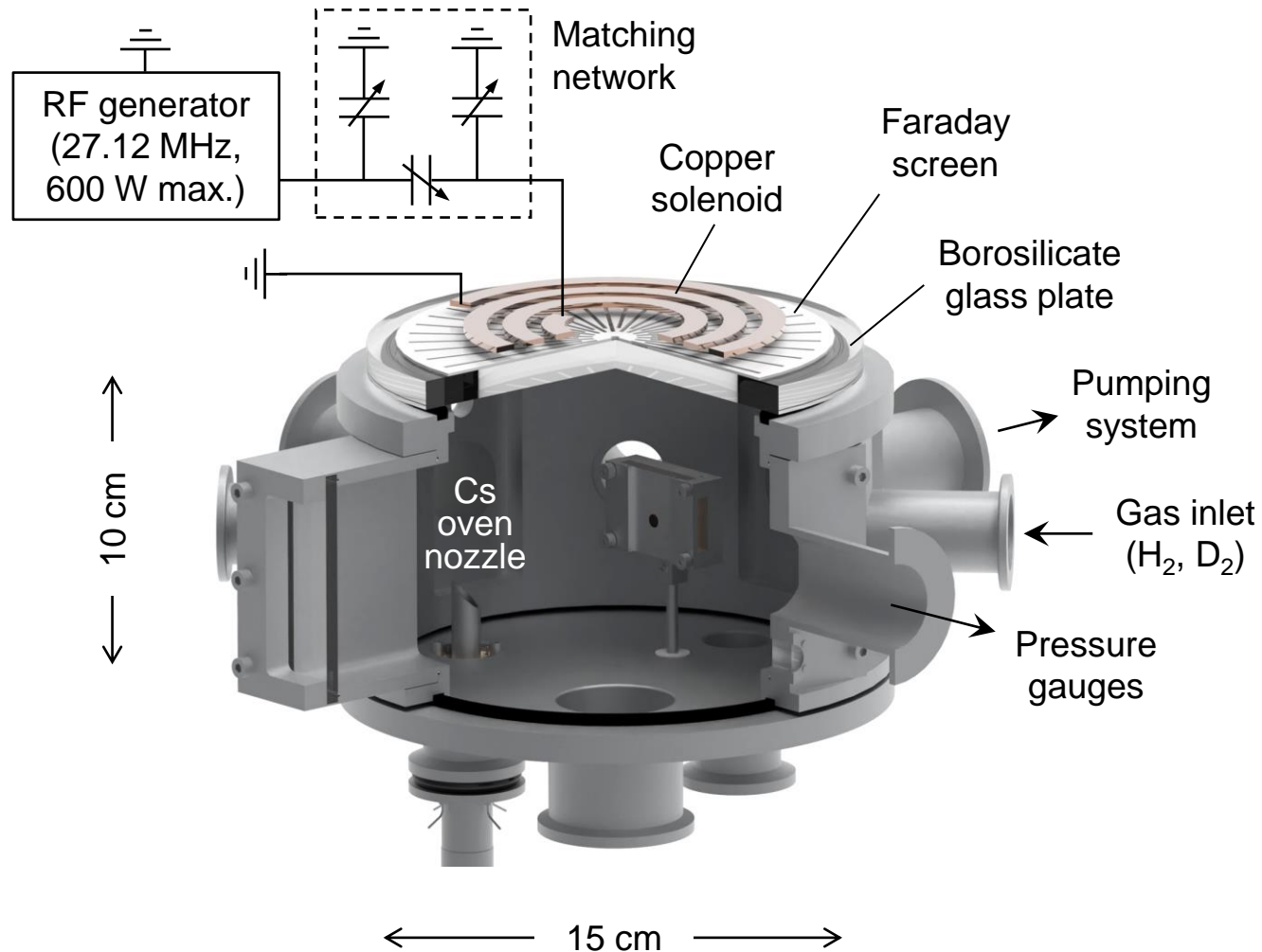
Base pressure: $10^{-6} - 10^{-5}$ mbar

→ Relevant to ion sources for fusion
(BUG and ELISE @ IPP,
SPIDER @ NBTF)

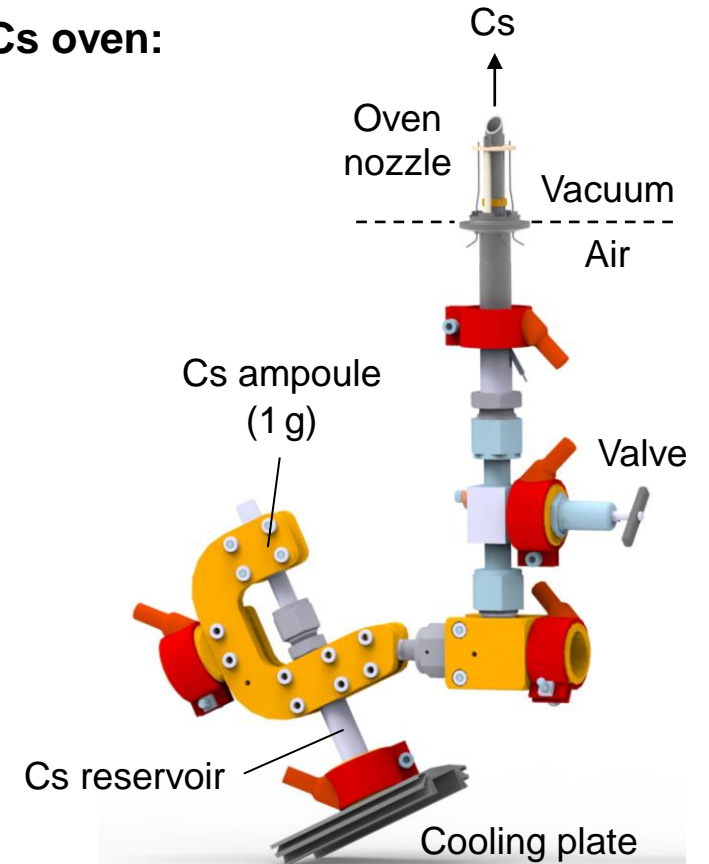


Experimental setup ACCesS

ICP experiment equipped with in situ work function diagnostic



Cs oven:

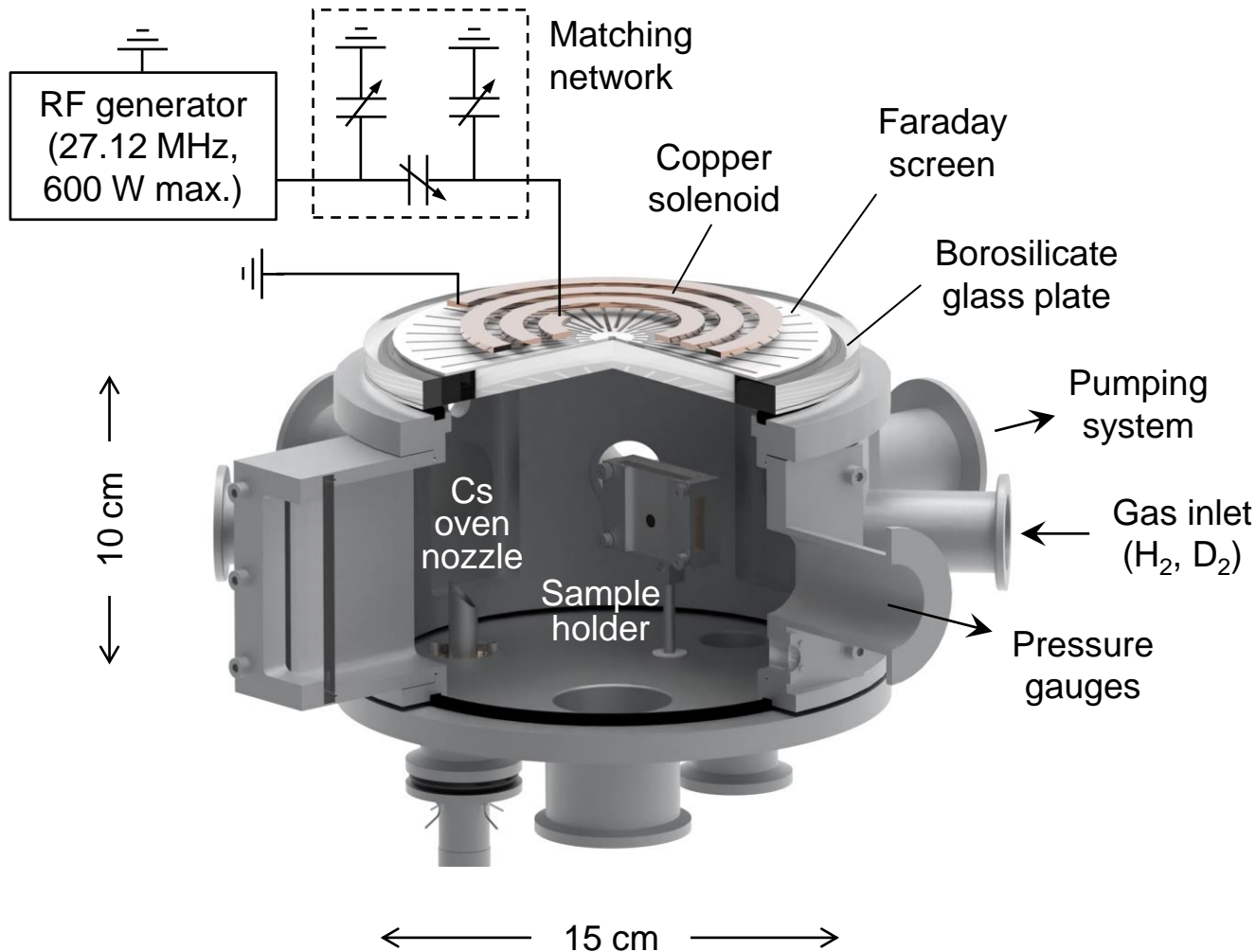


S. Cristofaro et al., *Rev. Sci. Instrum.* **90**, 113504 (2019)

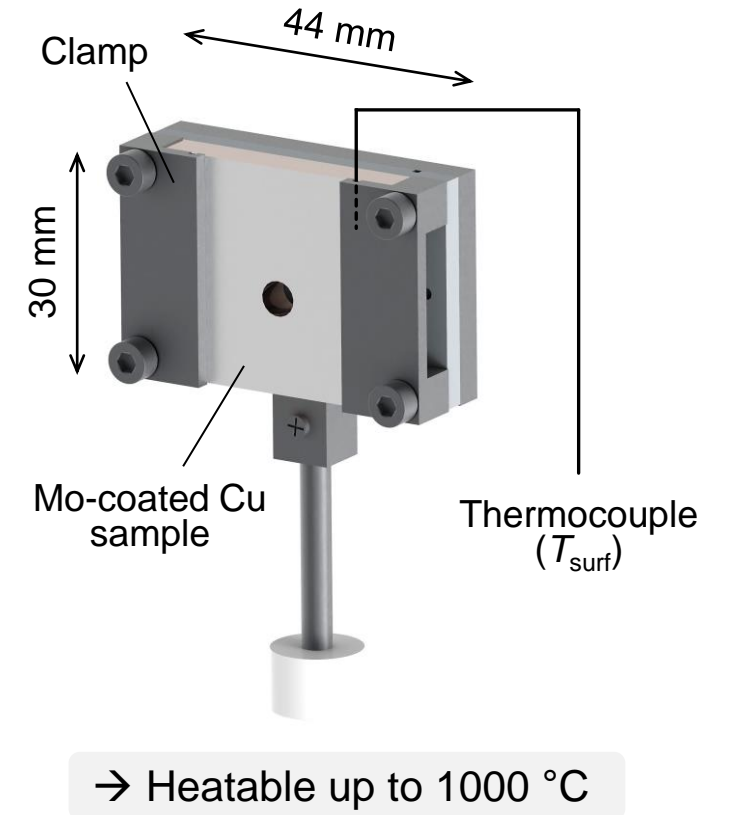


Experimental setup ACCesS

ICP experiment equipped with in situ work function diagnostic

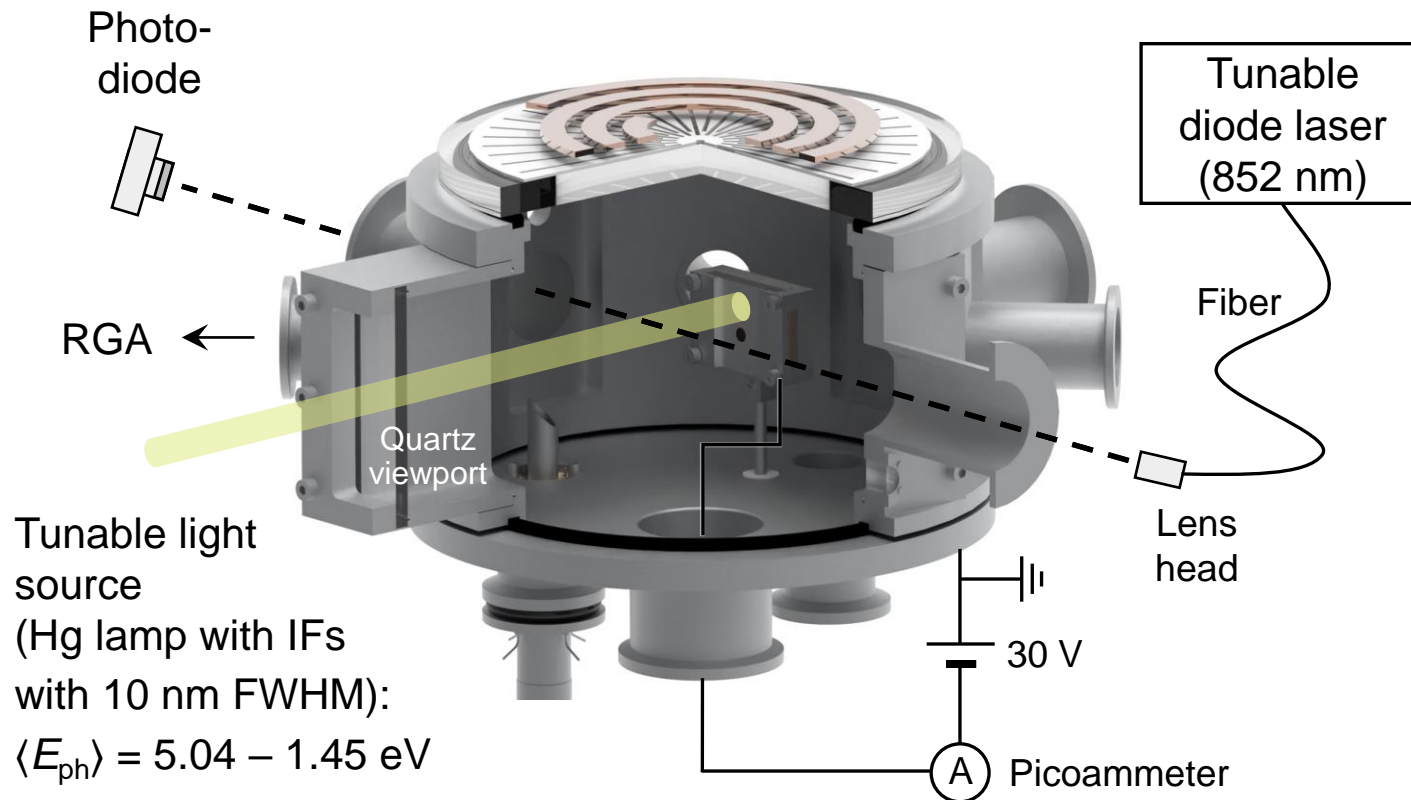


Sample holder:



Experimental setup ACCesS

ICP experiment equipped with in situ work function diagnostic

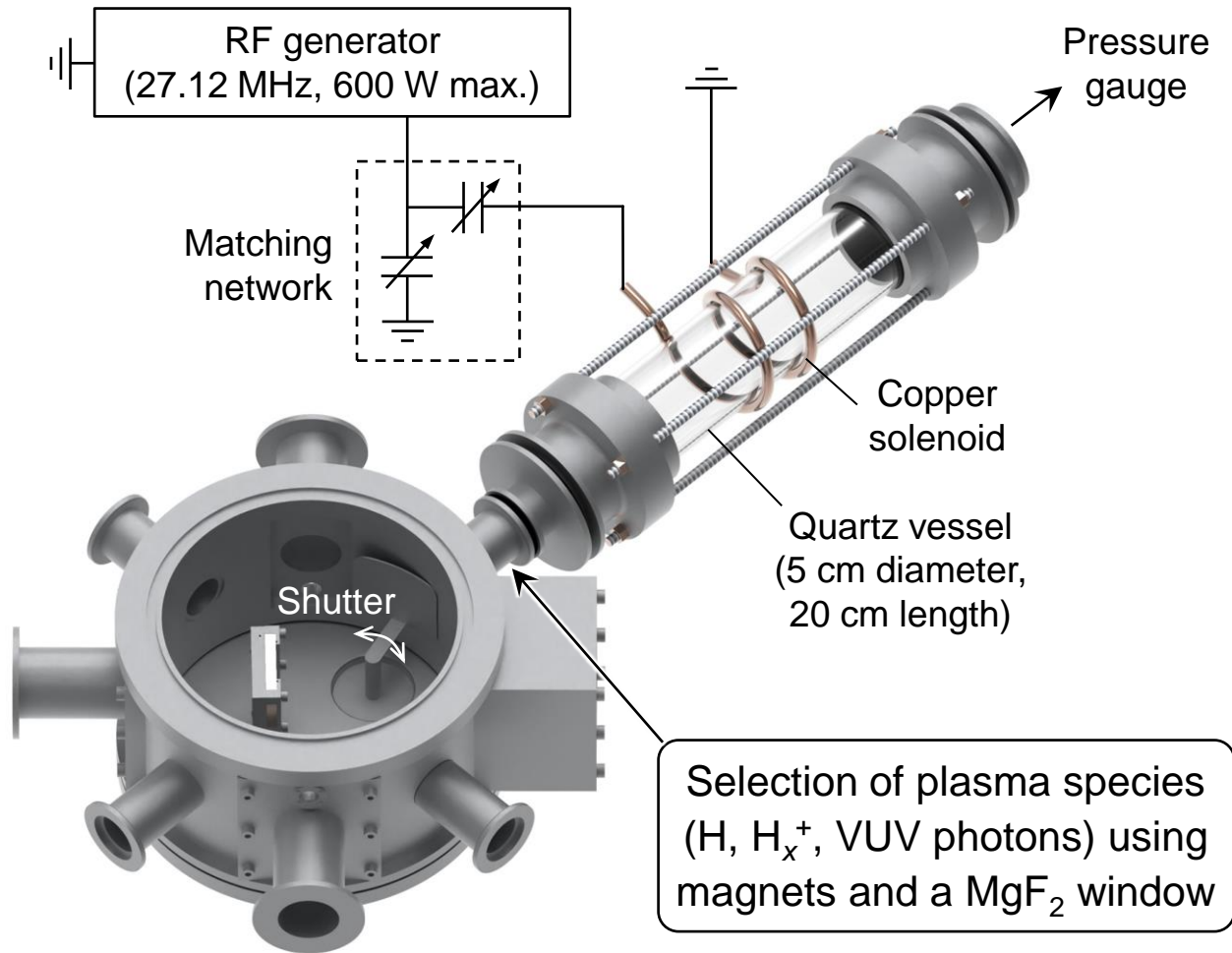


Diagnostics:

- Work function (WF) via photoelectric effect (Fowler method)
→ Improved threshold sensitivity
☞ A. Heiler *et al.*, *AIP Adv.* **12**, 035339 (2022)
- Neutral Cs density via TDLAS
- Gas composition monitored with RGA
- Plasma parameters:
 - Langmuir probe (Γ_{i+})
 - OES (Γ_{H})
 - VUV diagnostic (Γ_{VUV})
☞ R. Friedl *et al.*, A flexible diagnostic system for the quantification of VUV fluxes emitted from plasmas, submitted to *Meas. Sci. Technol.* (2022)

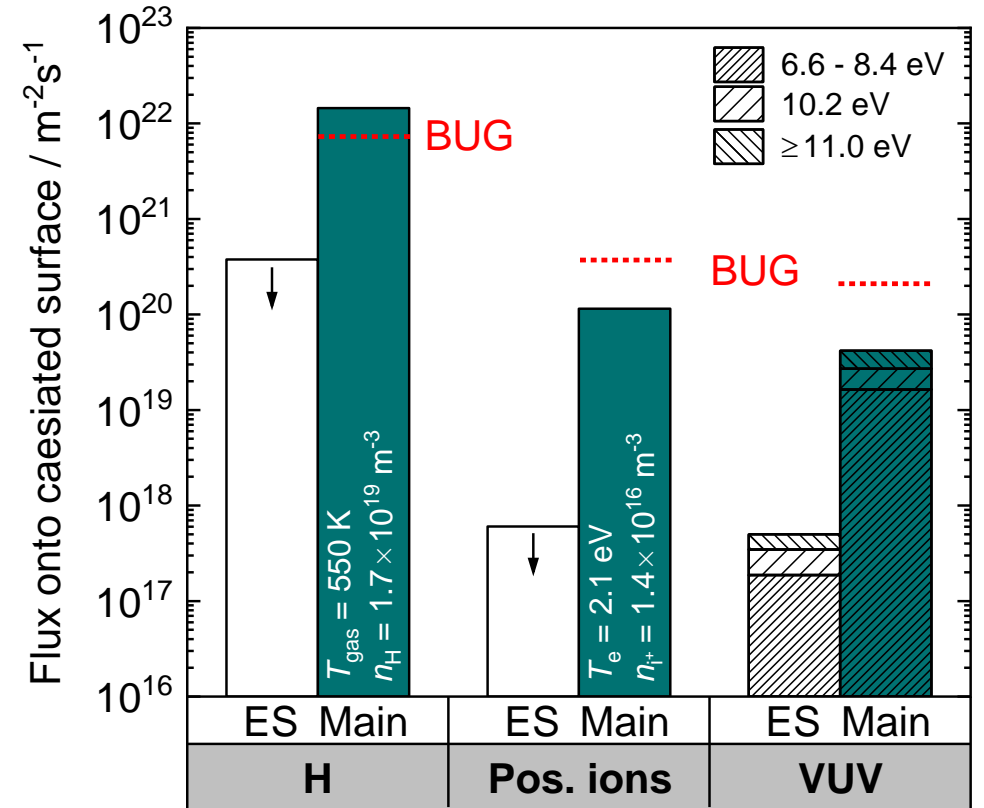
Upgrade of ACCesS experiment

External ICP source for selective exposure to hydrogen plasma species



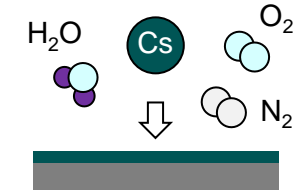
Fluxes onto caesiated surface from

- external source (ES) (10 Pa / 400 W)
- plasma in main vessel (Main) (10 Pa / 250 W)

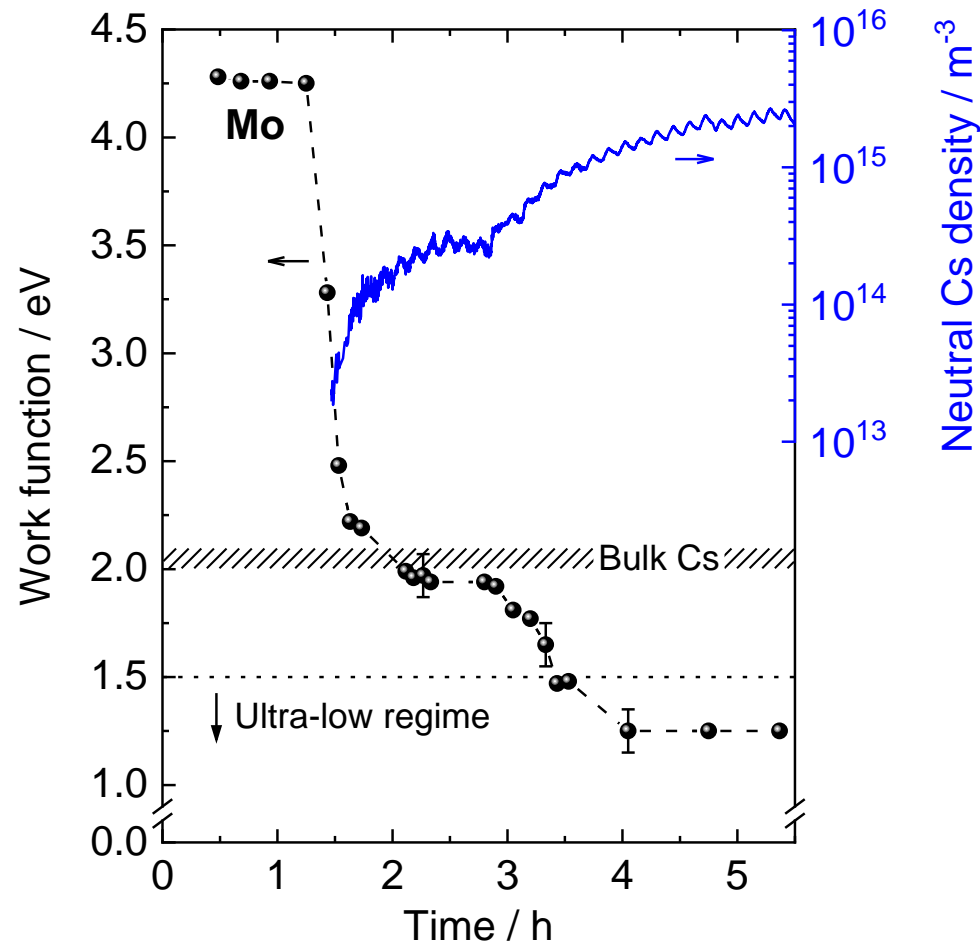


Caesiation under vacuum conditions of 10^{-6} – 10^{-5} mbar

Formation of ultra-low work function layer on Mo



A. Heiler et al., *AIP Adv.* 12, 035339 (2022)



Presence of Cs submonolayer coverage can be excluded:

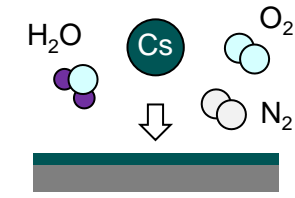
- WF_{\min} achievable with Cs coverage < 1 ML = 1.54 eV
Swanson and Strayer, J. Chem. Phys. 48, 2421 (1968)
- No WF increase with increasing Cs fluence
- Cs coating visible by eye



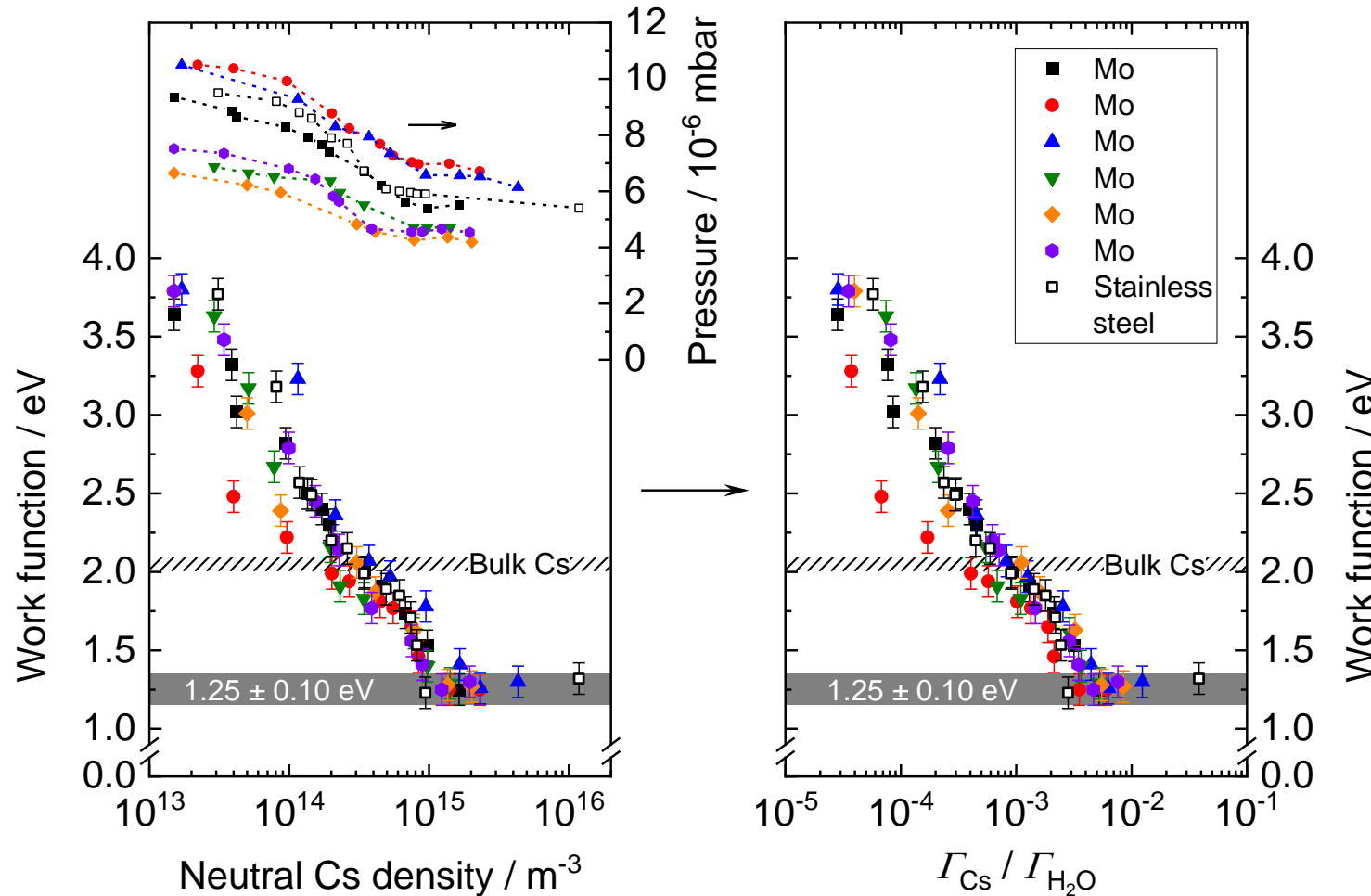
Growth of thick oxidized Cs layer due to reactions between Cs and residual H₂O

Caesiation under vacuum conditions of $10^{-6} - 10^{-5}$ mbar

Compilation of various caesiation processes



A. Heiler et al., *AIP Adv.* 12, 035339 (2022)



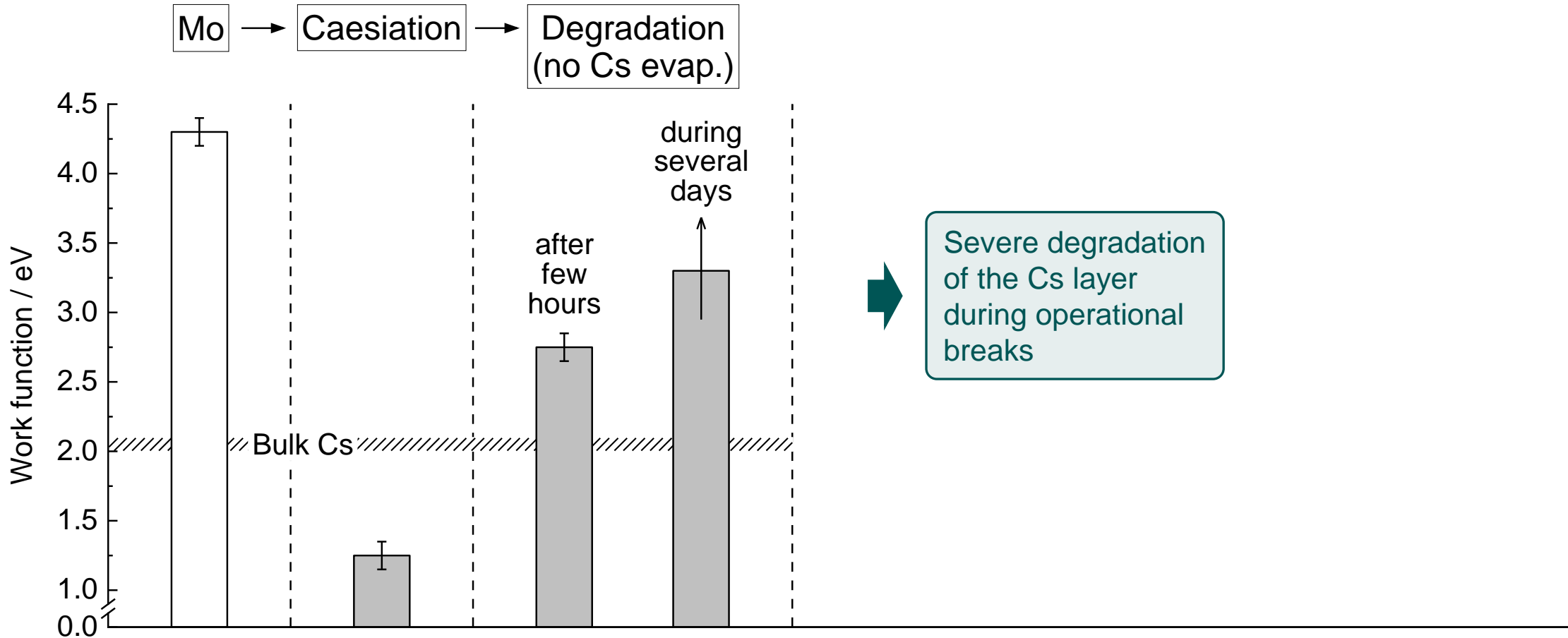
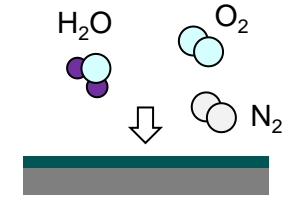
Excellent reproducibility:

- WF ~ 2 eV with Cs densities $\sim 10^{14} m^{-3}$
- WF = 1.2 – 1.3 eV with Cs densities $\gtrsim 10^{15} m^{-3}$, corresponding to a flux ratio of $\Gamma_{Cs} / \Gamma_{H_2O} \gtrsim 5 \times 10^{-3}$

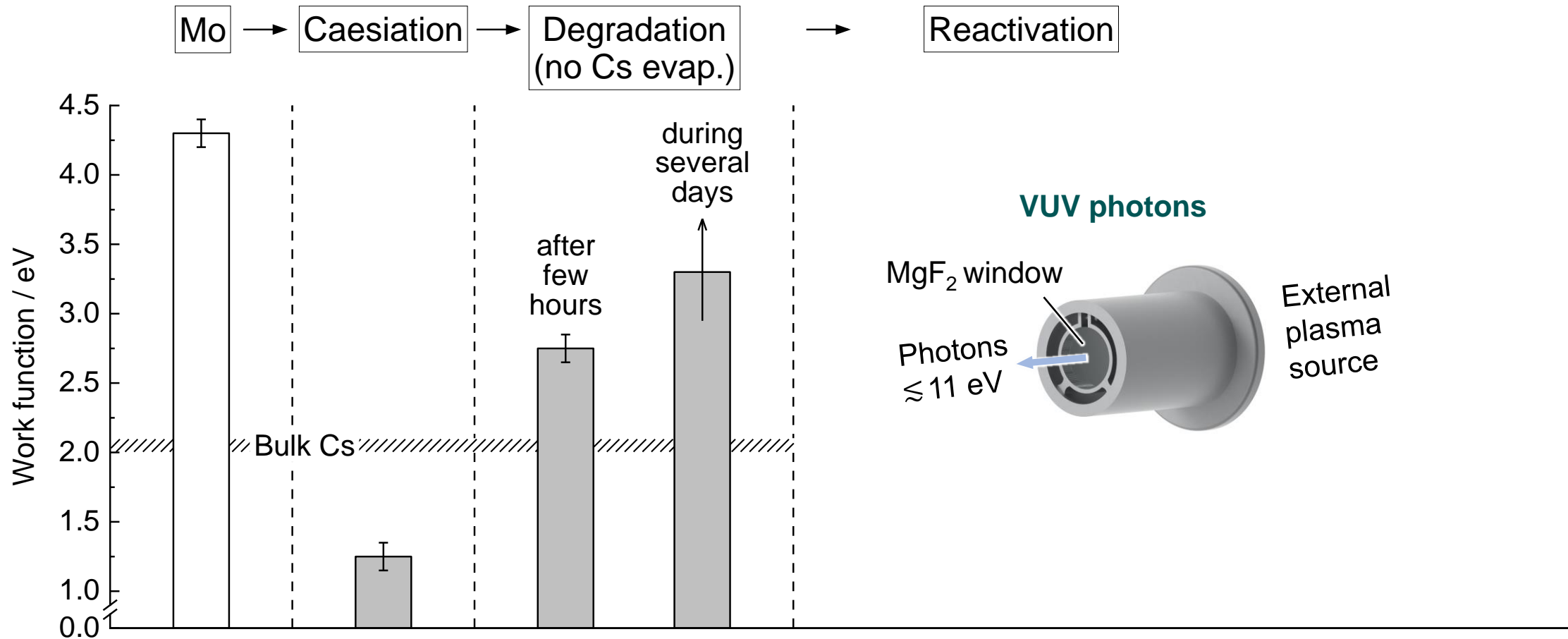
At BUG and ELISE ion sources:

$$\Gamma_{Cs} / \Gamma_{H_2O} = 3 - 9 \times 10^{-3}$$

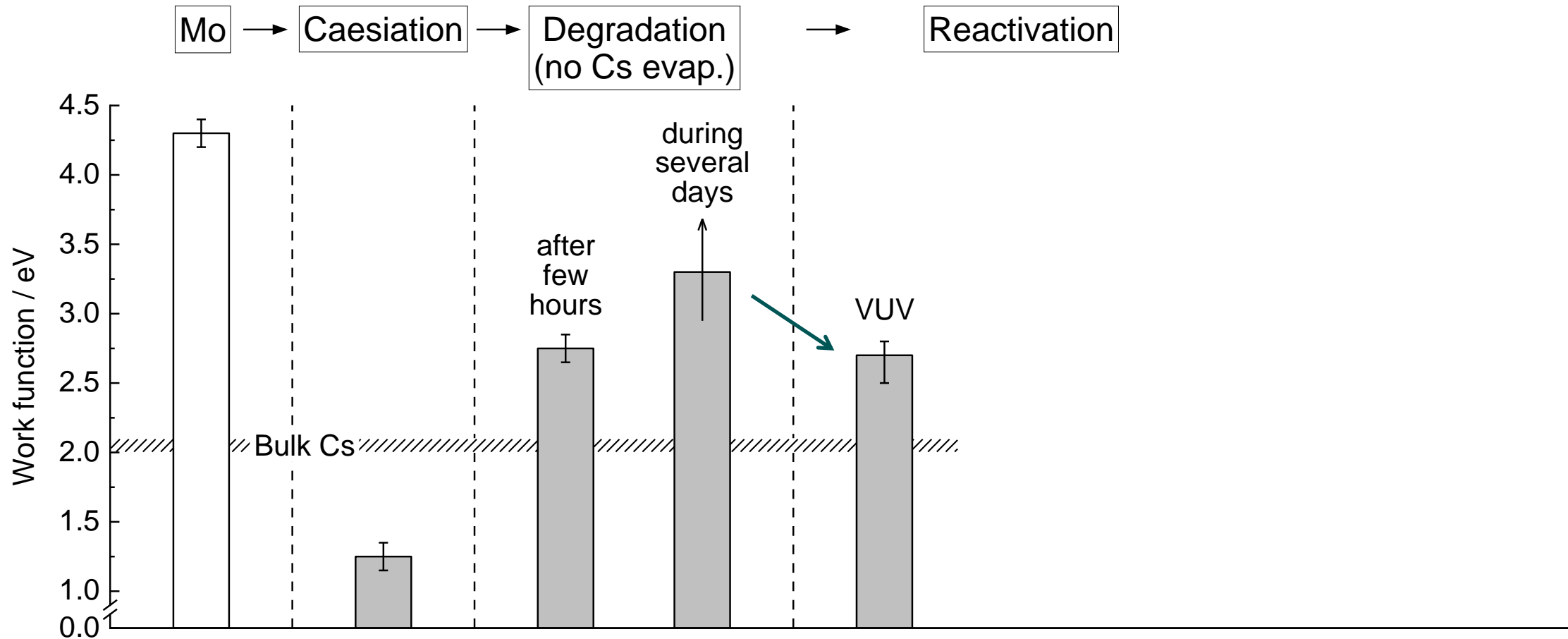
Degradation under vacuum conditions of 10^{-6} – 10^{-5} mbar



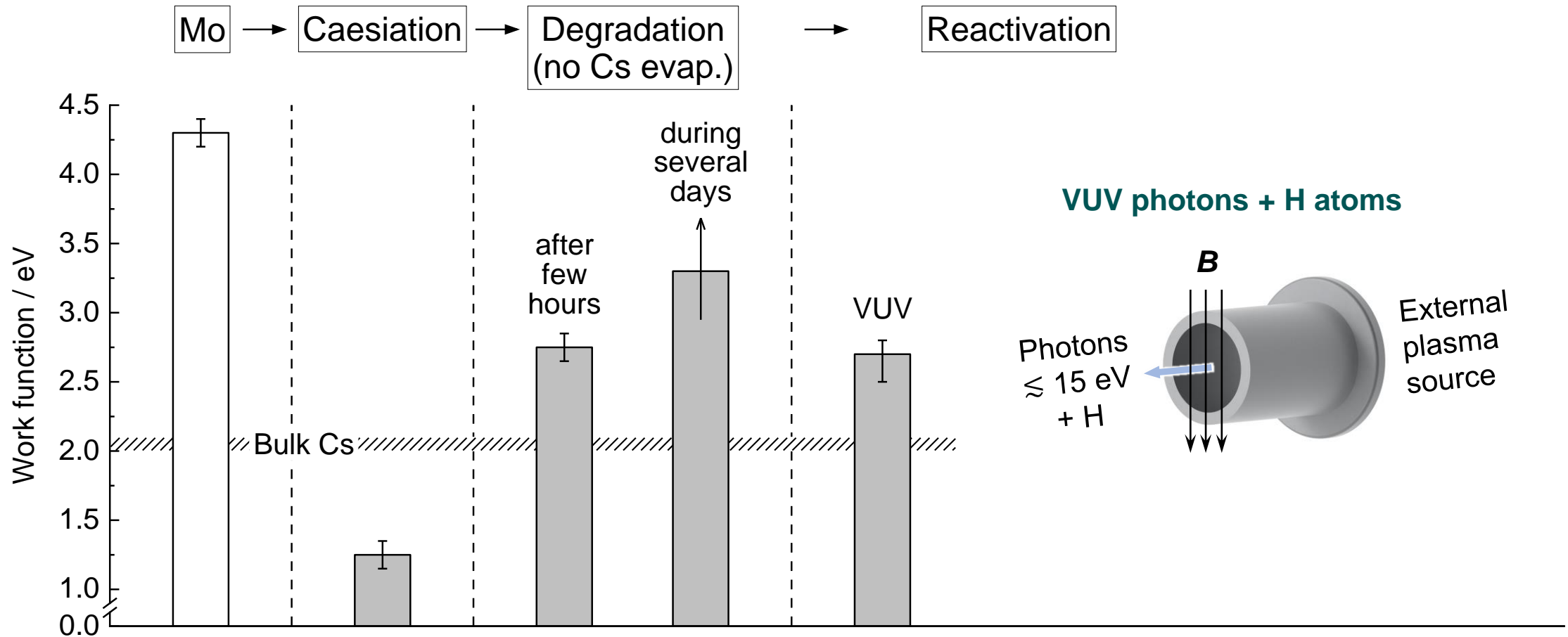
Impact of hydrogen plasma species on the WF of caesiated surfaces



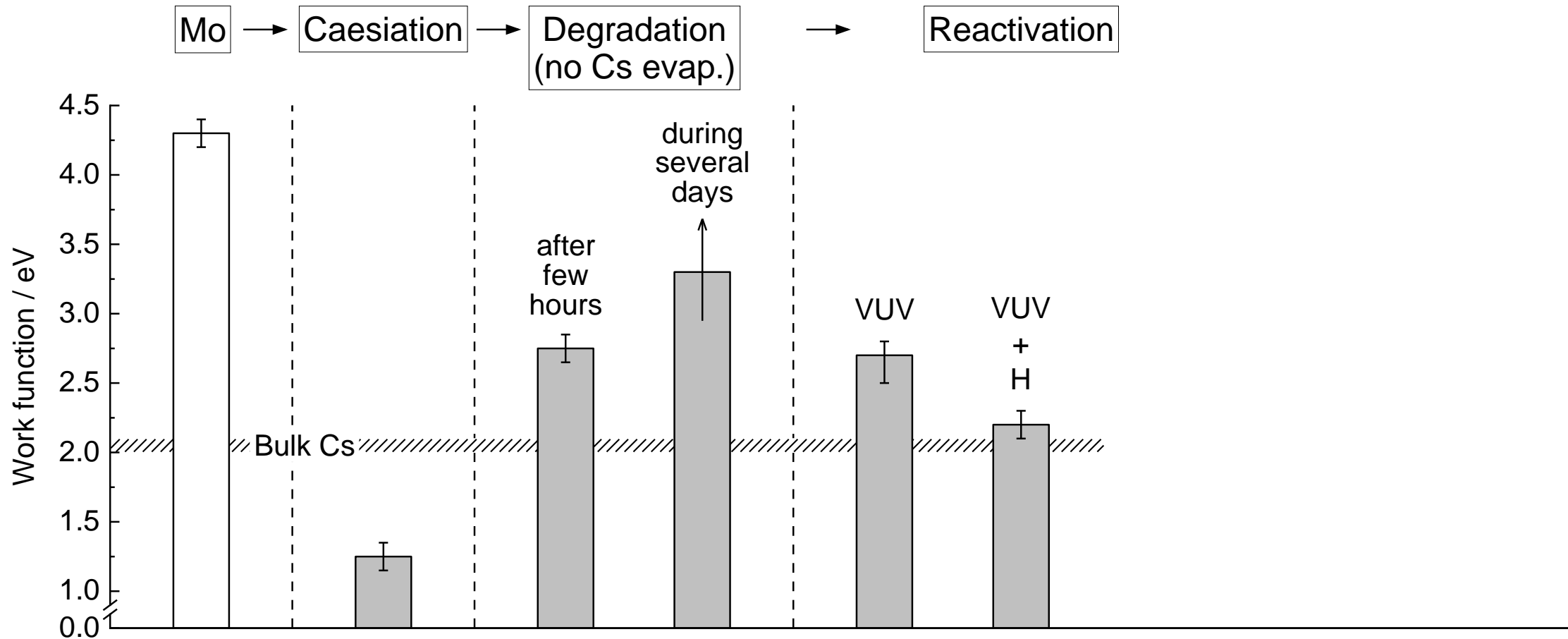
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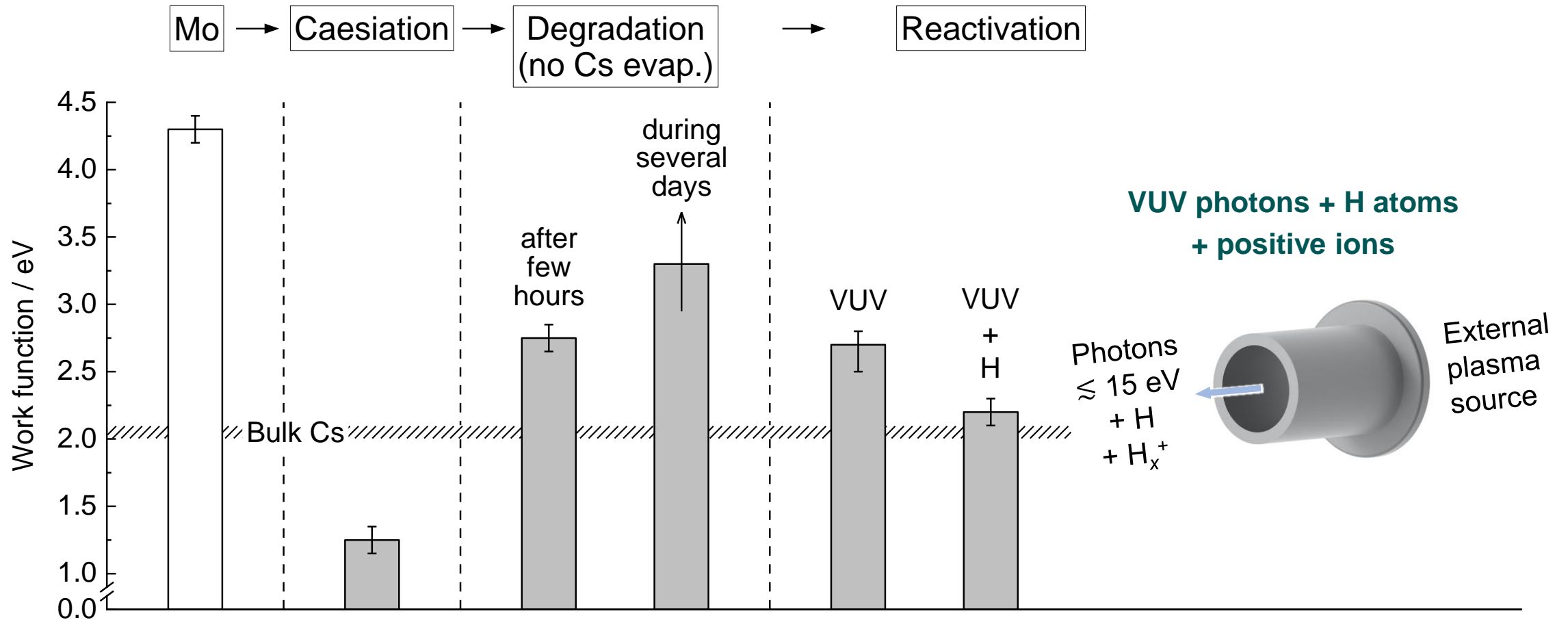
Impact of hydrogen plasma species on the WF of caesiated surfaces



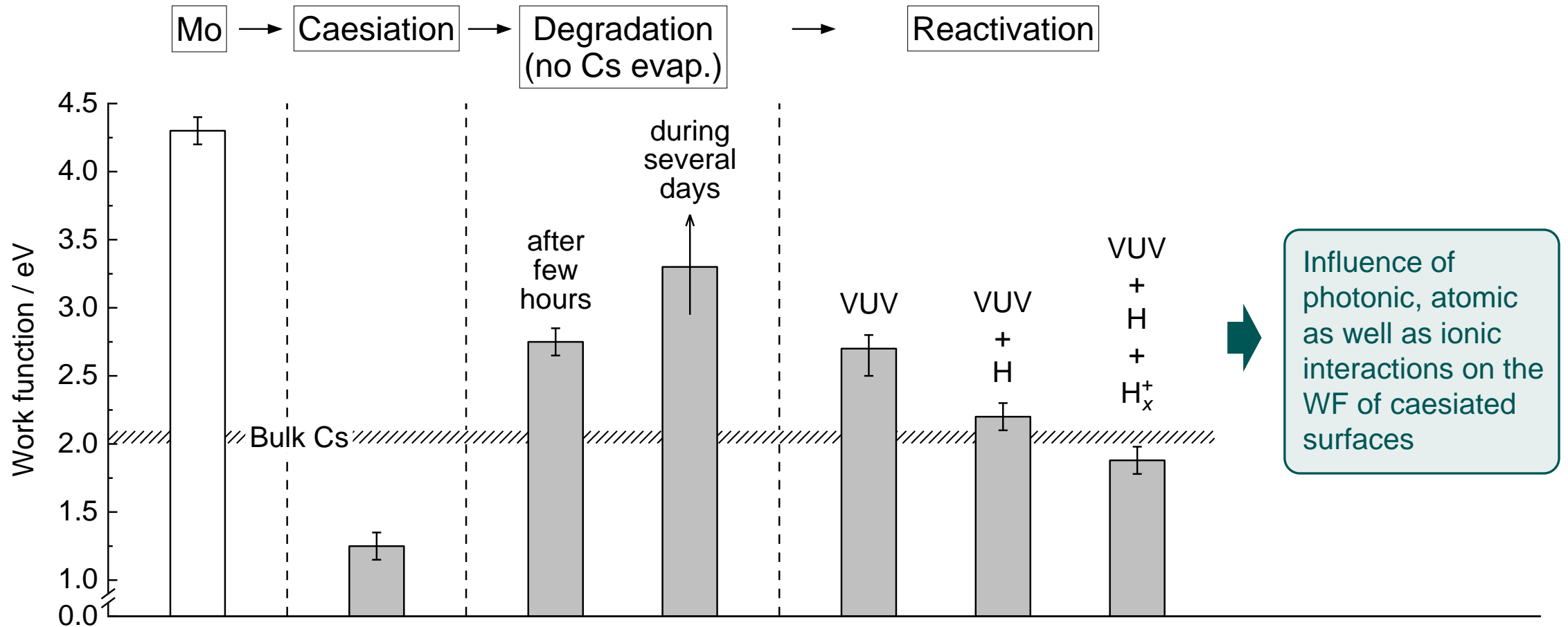
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Impact of hydrogen plasma species on the WF of caesiated surfaces

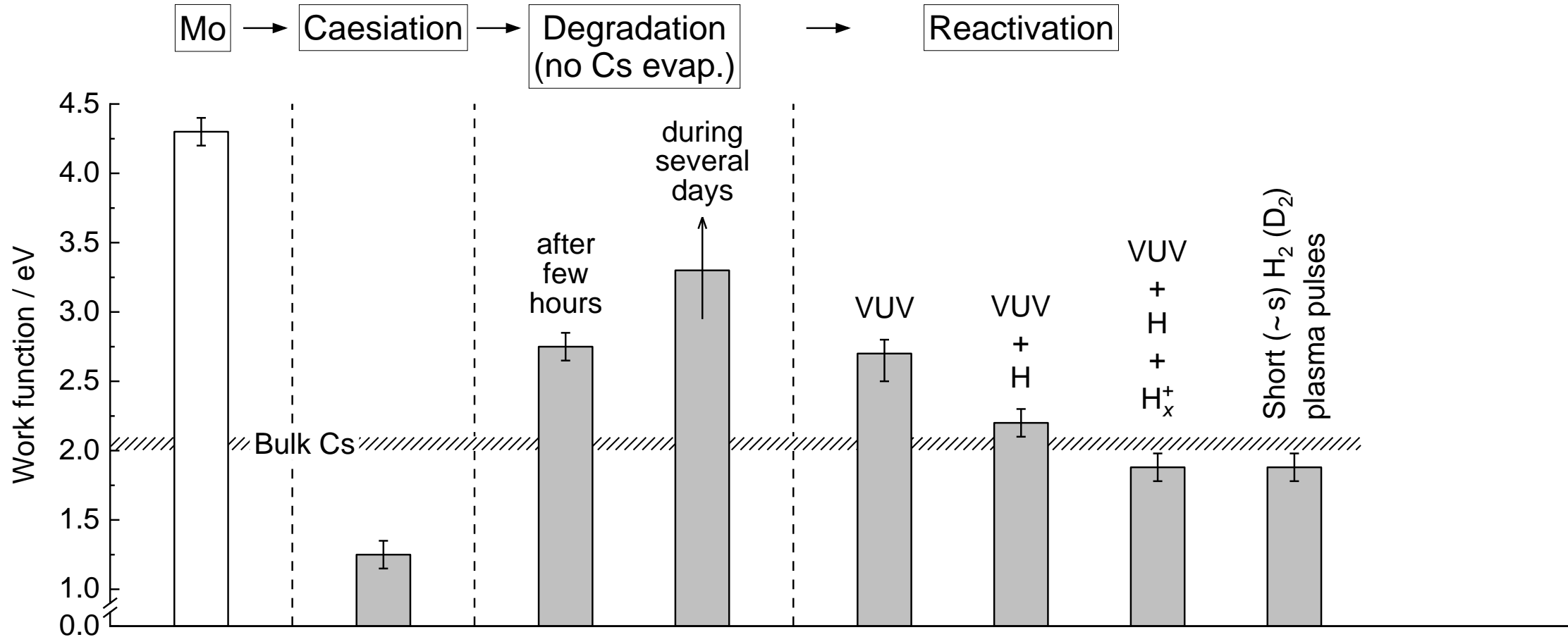
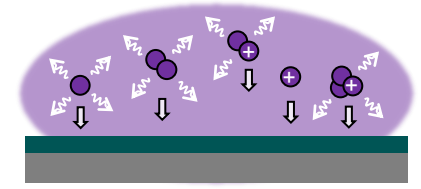


Impact of hydrogen plasma species on the WF of caesiated surfaces



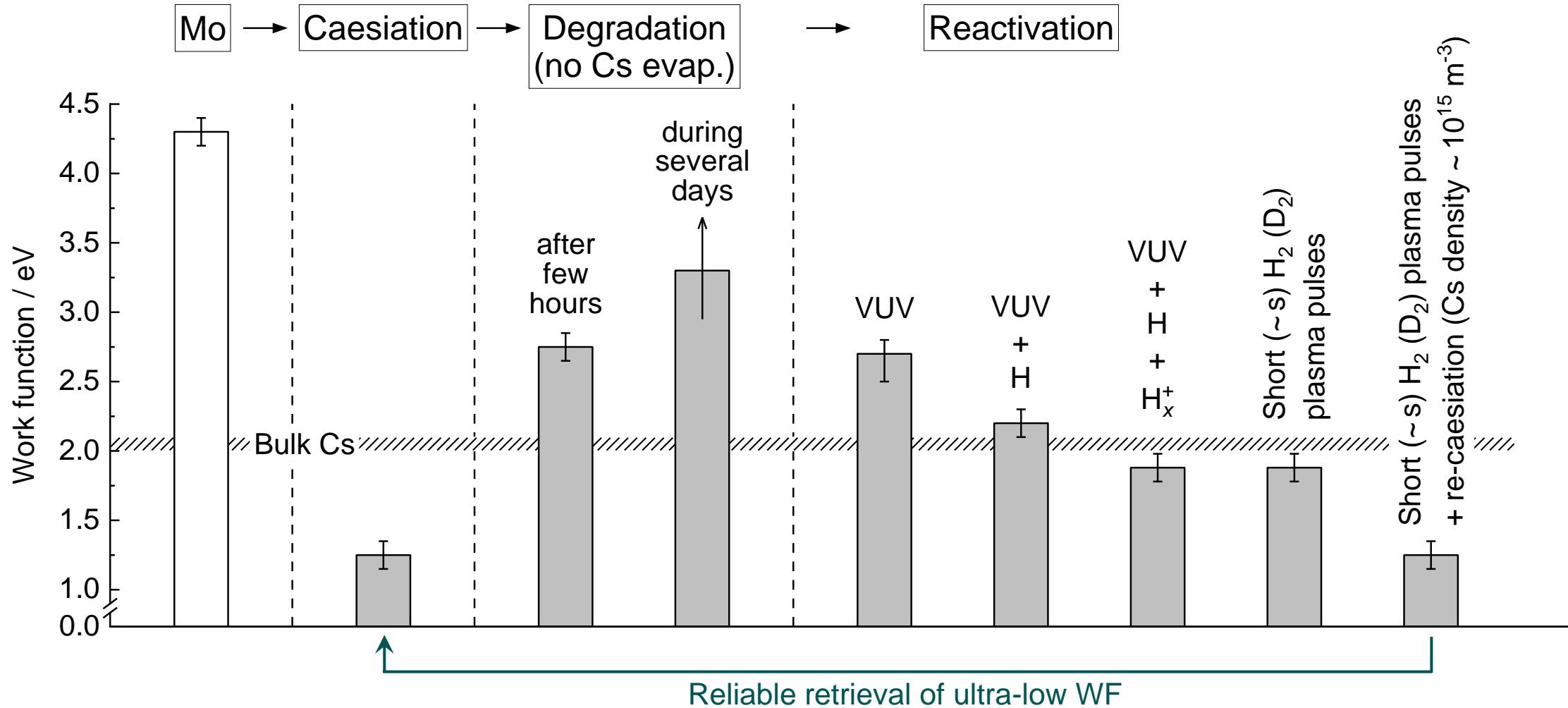
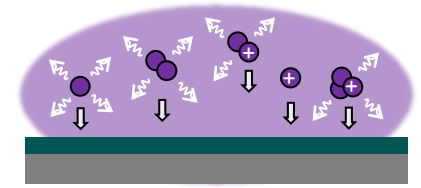
WF of caesiated surfaces upon H₂ (D₂) plasma exposure

Conditioning with short plasma pulses



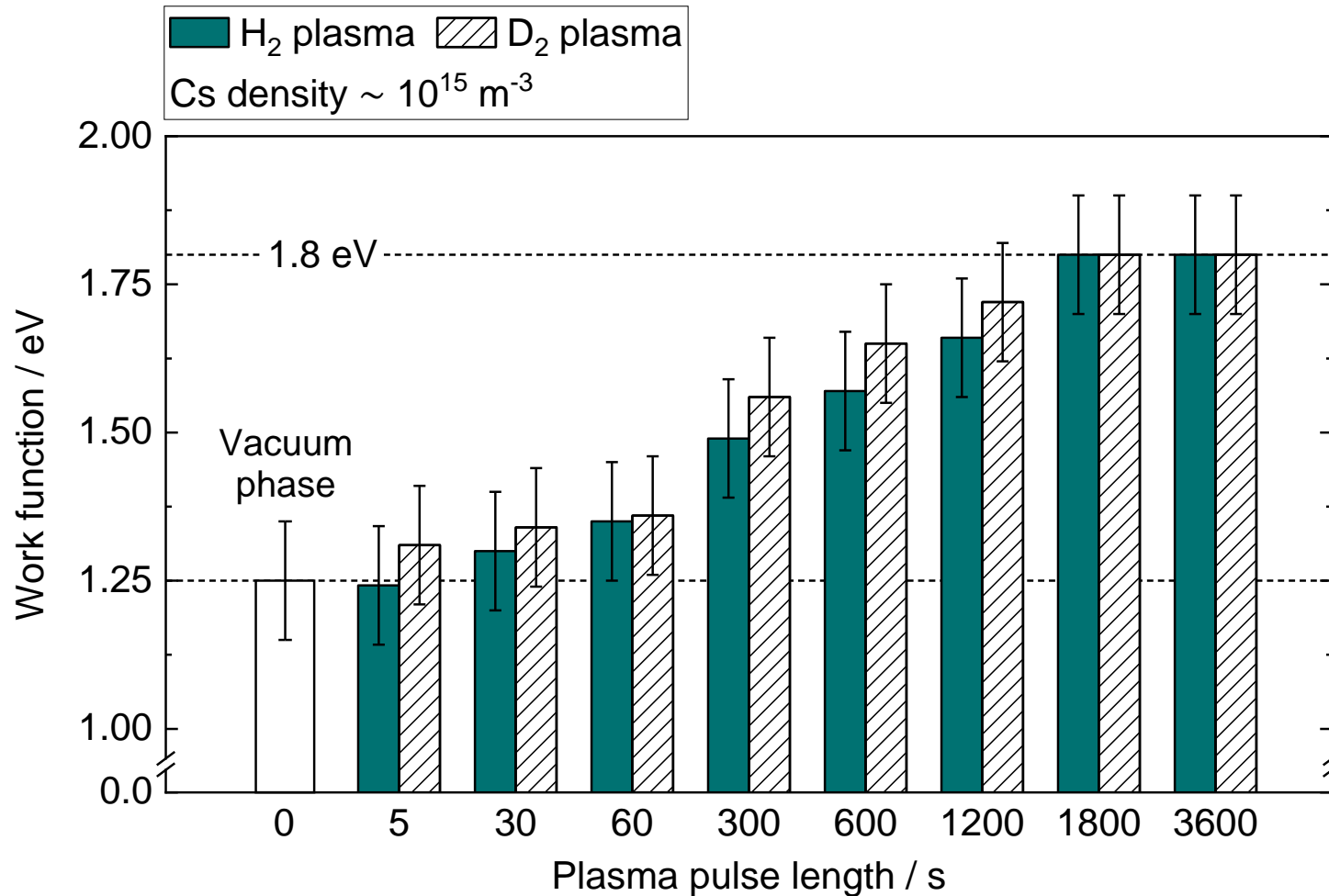
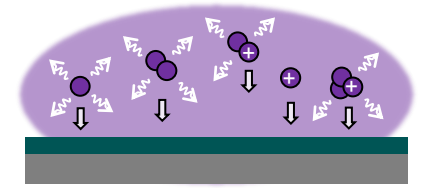
WF of caesiated surfaces upon H₂ (D₂) plasma exposure

Conditioning with short plasma pulses and Cs evaporation



WF of caesiated surfaces upon H₂ (D₂) plasma exposure

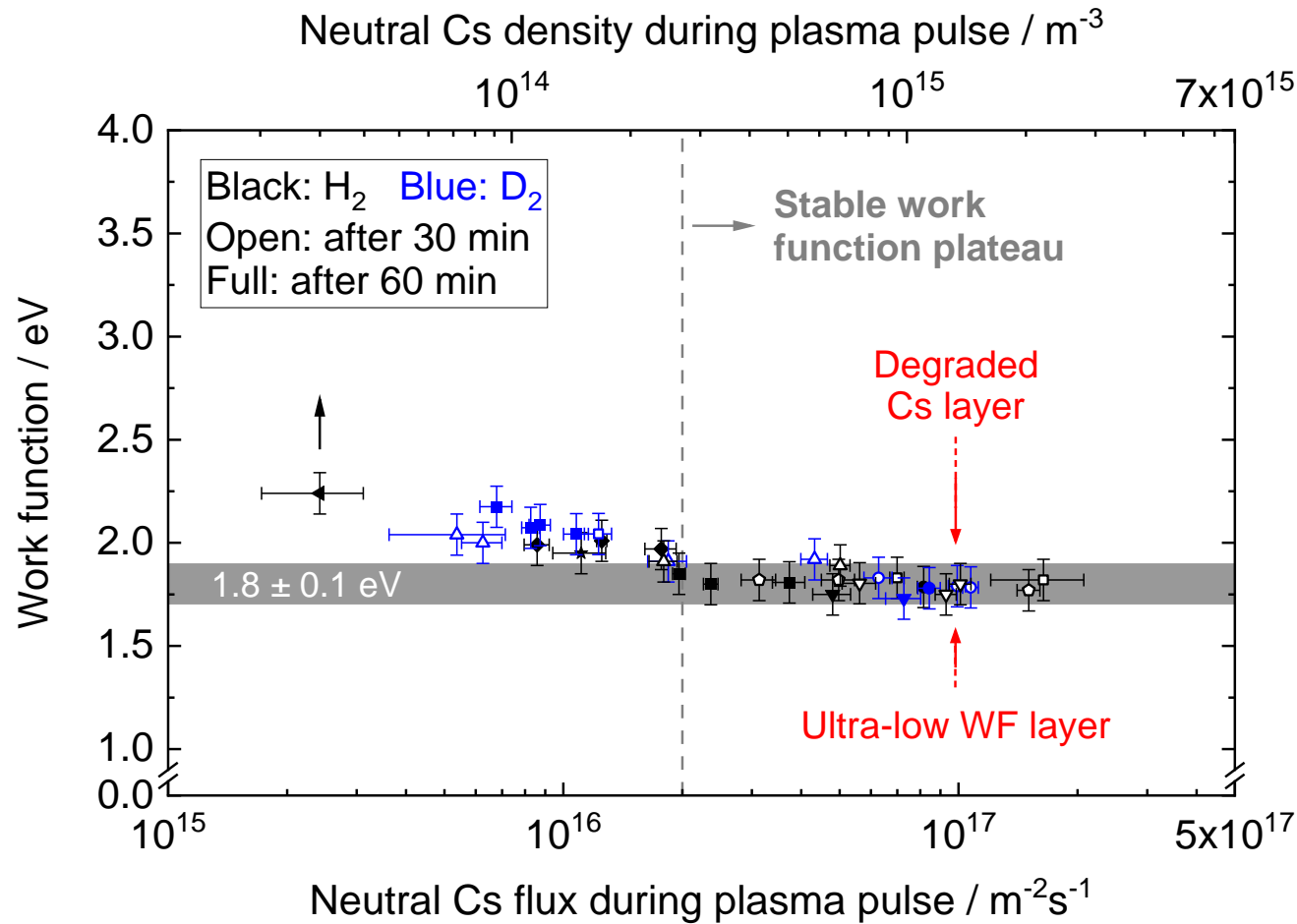
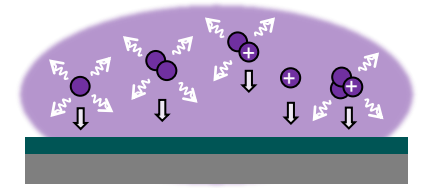
Durability of ultra-low work function layer



Ultra-low WF layer only stable up to H₂ (D₂) plasma exposures of ~ 1 min
→ Hints for temporal deterioration of ion source performance

WF of caesiated surfaces upon H₂ (D₂) plasma exposure

Steady-state plasma operation



- Stable WF of 1.8 ± 0.1 eV for Cs densities $\geq 3 \times 10^{14} \text{ m}^{-3}$ (Cs fluxes $\geq 2 \times 10^{16} \text{ m}^{-2}\text{s}^{-1}$) during plasma phase
- Reached WF independent of initial WF in the vacuum phase

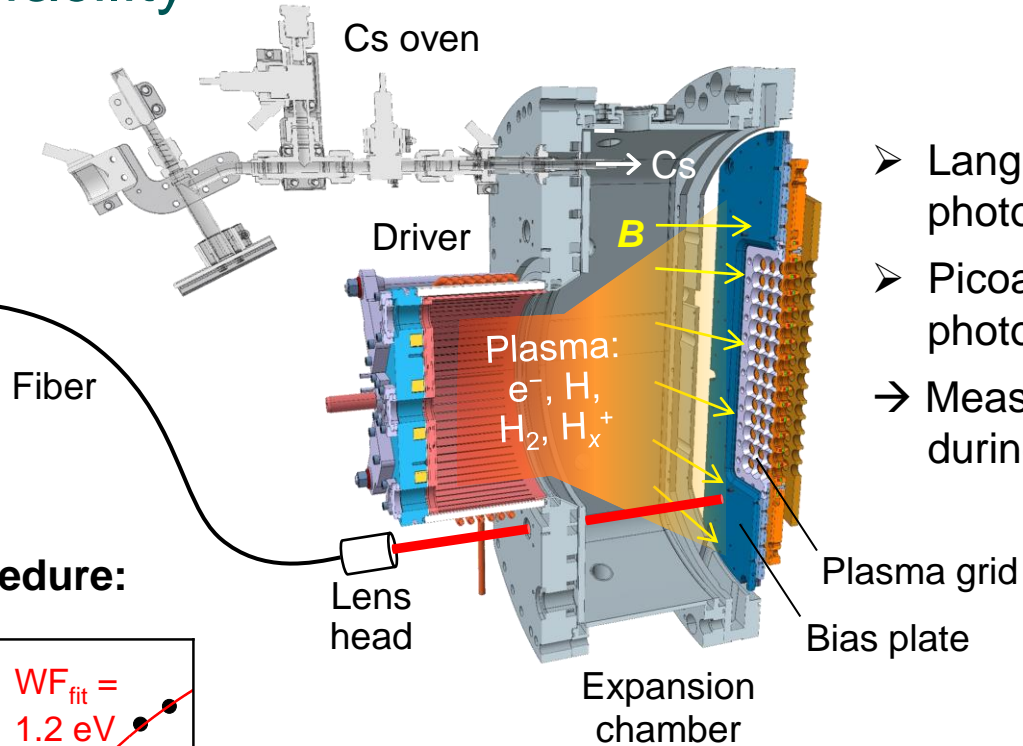
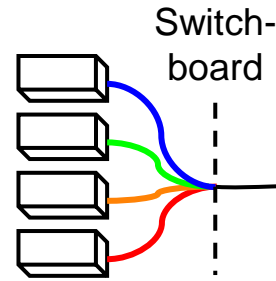
Development of WF diagnostic for ion sources using LEDs

Proof of concept at BUG test facility

Poster by
J. Berner
(session 2)

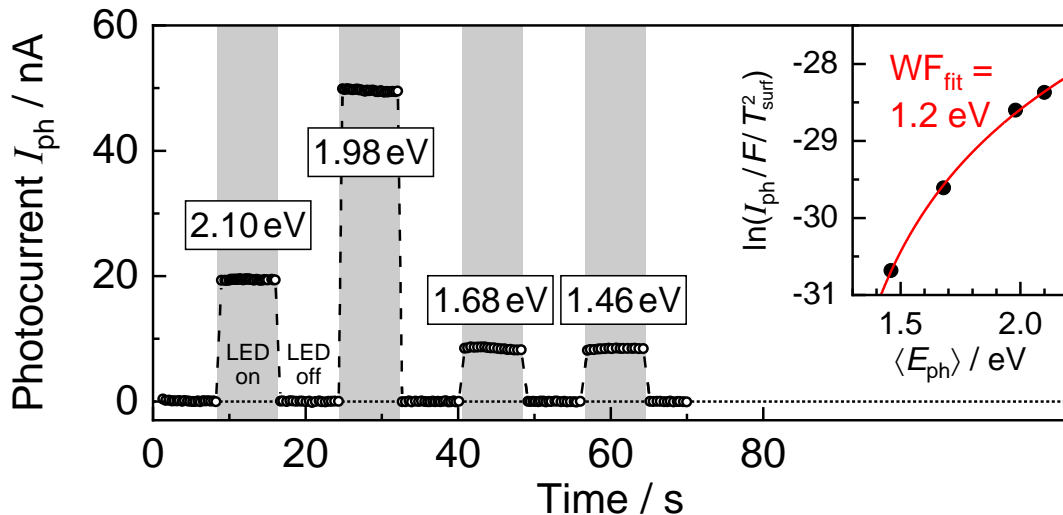


Fiber-coupled LEDs:
 $\langle E_{ph} \rangle = 3.22 - 1.13 \text{ eV}$
 FWHM = 15 - 30 nm



- Langmuir probe used as photoelectron collector
- Picoammeter used for photocurrent measurement
- ➔ Measurements possible during plasma-off phases

Measurement during Cs conditioning procedure:



WF < 2 eV confirmed

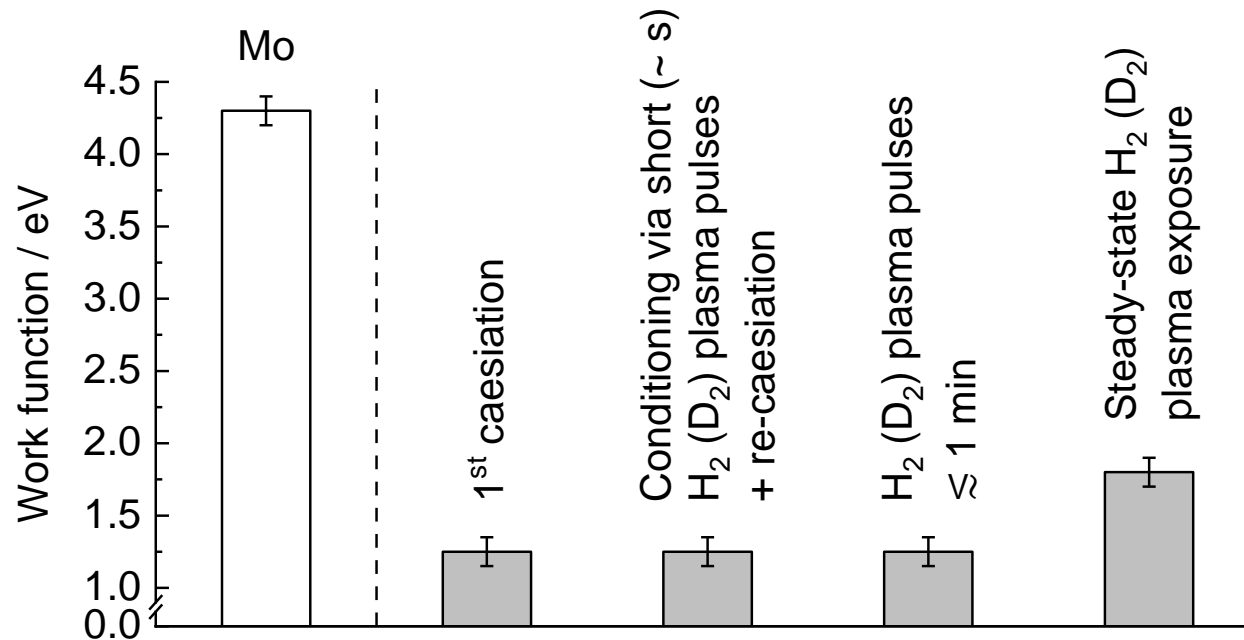


Proof of concept for absolute WF measurements ✓



Summary and outlook

- **Caesiation under vacuum conditions of $10^{-6} - 10^{-5}$ mbar:**
 - Reliable formation of Cs layers with ultra-low WF in the range of 1.2 – 1.3 eV
 - Figure of merit: $\Gamma_{\text{Cs}}/\Gamma_{\text{H}_2\text{O}}$
- **WF of caesiated surfaces influenced by impinging VUV, H and H_x^+ species**
- **WF dynamics of caesiated surfaces upon H_2 (D_2) plasma exposure:**



- **Next steps:**

- Systematic investigations on the correlation between WF, plasma parameters and extracted H^- / e^- currents at BUG test facility
- Investigations on WF dynamics at lab experiment with lower background pressure ($10^{-6} \dots 10^{-9}$ mbar)